

Title (en)
SUBSTRATE CLEANING APPARATUS AND METHOD

Title (de)
VERFAHREN ZUR REINIGUNG VON EINEM SUBSTRAT UND EINRICHTUNG DAFÜR

Title (fr)
APPAREIL ET PROCEDE DE NETTOYAGE DE SUBSTRAT

Publication
EP 1297566 A2 20030402 (EN)

Application
EP 01944538 A 20010614

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Abstract (en)
[origin: WO0197270A2] A substrate (30) may be cleaned by exposing the substrate (30) to an energized stripping gas while maintaining the substrate (30) at a first temperature and exposing the substrate (30) to an energized passivating gas while maintaining the substrate (30) at a second temperature. In another version, the substrate (30) is stripped and passivated in separate chambers. A cleaning chamber (120) may be provided with a heater (320) to heat the top of the substrate (30)

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H01L 21/3213; **H01J 37/32**

IPC 8 full level
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